Response Under 37 CFR 1.116
Expedited Procedure
Examining Group 2873

Remarks

Headings of this AAFA correspond to the headings of the AAFA.

Specification

The title of this application is changed as follows:

Projection Objective for Microlithography

A substitute specification without the claims (pages 17-21) filed under 37

CFR1.125(a) is submitted herewith The substitute specification contains only subject matter from the original specification.

Claim Rejections under 35 USC 102(b)

Claims 5, 6, 10 and 22 are rejected as anticipated by Sasaya et al. (Sasaya) or

Yamaguchi et al (Yamaguchi) or Afaki

DE 198 18 444 A1 is also US 6,008,884.

Claims 5, 6 and 10 are cancelled.

Claim 8 is amended by explicitly entering former claims 5 and 6.

Claim 22 is cancelled.

Claims 23 and 24 take the wording from claim 22 and the values of claims 23 and

24.

A Terminal Disclaimer concerning pending application 09/847,658, filed May 2,

2001, is submitted herewith.

US Patent Application 09/760,066 (Z) 99023 P US Schuster

Response Under 37 CFR 1.116 Expedited Procedure Examining Group 2873

Wherefore, further consideration and allowance of the claims is respectfully requested.

A three-month extension of time in which to respond to the outstanding Office Action is hereby requested. A PTO 2038 authorizing credit card payment for the amount of \$950 is enclosed for the prescribed Large Entity three-month extension fee, \$110 for the terminal disclaimer fee and \$330 for the Notice of Appeal fee. Any other fees due by virtue of this filing or this application should be charged to Deposit Account 11-0665. Any refunds in connection with this filing should be credited to Deposit Account 11-0665. A duplicate of this page is enclosed for this purpose.

Respectfully submitted,

M. Robert Kestenbaum

Reg. No. 20,430

11011 Bermuda Dunes NE

Albuduerque, NM USA 87111

M. Oar Letylon

Telephone (505) 323-0771

Facsimile (505) 323-0865

I hereby certify this correspondence is being submitted to Commissioner for Patents, Alexandria, VA, 22313 by facsimile transmission on March 30, 2004p, fax number (703) 872-9306.

M. Robert Kestenbaum

US Patent Application 09/760,066 (Z) 99023 P US

Schuster

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Reg. No. 20,430

1101 Bermuda Dunes NE

Albuquerque, NM USA 87111

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US Patent Application 09/760,066 (Z) 99023 P US Schuster

Projection Objection Objective for Micr lith graphy

Cross References to Related Applications

This application is a continuation application of PCT/EP99/10233, which is pending.

German Applications DE 198 55 108A, DE 198 55 157A, and DE 198 55 158A, in which the Applicant participated, are incorporated herein by reference.

Statement Regarding Federal Sponsored Research or Development - Not Applicable.

Reference to a Microfiche Appendix – Not Applicable.

Background of the Invention

Technical Field

The invention relates to a projection objective with a lens arrangement, which can be divided into six lens groups. The first, third, fifth and sixth lens groups have positive power and the second and fourth lens groups respectively have negative power. The division of the lens system into lens groups is described in more detail hereinafter, based on the direction of propagation of the radiation.

The first lens group is positive and ends with a lens of positive power. A bulge is formed by the first lens group; it is unimportant if negative lenses are also arranged in the bulge.

The second lens group is of negative total power. This second lens group has as its first lens a lens having a concave lens surface toward the image. This second lens group substantially describes a waist. Here, also it is not of substantial importance if a few positive lenses are included in the second lens group, as long as the waist is maintained.

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

The third lens group begins with a lens having positive power and a convex lens surface on the image side, and which can be a meniscus. If a thick meniscus lens is provided as the first lens, the separation of the lens groups can be considered to be within the lens.

The fourth lens group is of negative power. This fourth lens group begins with a lens of negative power, followed by several lenses having negative power. A waist is formed by this lens group. It is unimportant if lenses having positive power are also contained within this lens group, as long as these influence the course of the beam over only a short distance and thus the waisted shape of the fourth lens group is maintained.

The fifth lens group has positive power overall. The first lens of this fifth lens group has a convex lens surface on the image side. A bulge is formed by the fifth lens group.

After the lens of maximum diameter (the bulge), there follow at least an additional two positive lenses in the fifth lens group, further negative lenses also being permitted.

The sixth lens group is likewise positive in its total power. The first lens of the sixth lens group is negative and has on the image side a concave lens surface. This first lens of the sixth lens group has a considerably smaller dameter in comparison with the maximum diameter of the bulge.

Background Art

Such projection objectives are in particular used in microlithography. They are known, for example, from the German Applications DE 198 55 108A, DE 198 55 157A, and DE 198 55 158A, in which the Applicant participated, and from the state of the art cited therein. These documents are incorporated herein by reference.

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

These projection objectives are issually constructed from purely spherical lenses, since the production and testing technology is advantageous for spheres.

Projection objectives are known from German Application DE 198 18 444 A1 which have lenses having aspheric surfaces in at least the fourth or fifth lens group. An increase of the numerical aperture and of the image quality can be attained by means of the aspheric surfaces. The projection objectives shown have a length from the mask plane to the image plane of 1,200 mm to 1,500 mm. A considerable use of material is associated with this length. High production costs are entailed by this use of material, since because of the required high image quality only high quality materials can be used. Aspheric lenses up to a diameter of about 300-mm are required, the provision of which is particularly expensive. It is not at all clear in the technical world whether aspheric lenses with such large lens diameters can be provided in the required quality. "Aspheric surfaces" are understood to include all surfaces which are not spherical and which are rotationally symmetrical. Rotationally symmetrical splines can also be considered as aspheric lens surfaces.

Summary of the Invention

The invention has as its object to provide a projection objective which has as few lenses as possible, with reduced use of material, the aspheric lens surfaces used being as few and as small as possible, with the lowest possible asphericity. A high aperture projection objective of short structure is to be cost-efficiently provided in this way.

The object of the invention is attained in particular by a projection objective for microlithography having a lens arrangement comprising a first lens group having positive power;

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

a second lens group having negative power; a third lens group having positive power; a fourth lens group having negative power; a fifth lens group having positive power; and a sixth lens group having positive power; wherein a lens at the end of the second lens group, particularly the last lens of the second lens group, or a lens at the beginning of the third lens group, particularly the first lens of the third lens group, has an aspheric surface. In addition, the object of the invention is attained by a projection objective having a lens arrangement having at least a first waist of a pencil of rays, wherein the lens arrangement comprises at least one of the following: a lens having an aspheric surface arranged before the first waist, a lens having an aspheric surface arranged after the first waist, and lenses having aspheric surfaces arranged before and after the first waist.

In a projection objective with a lens arrangement, by the measure of providing, in the forward half of this lens arrangement, at least one lens provided with an aspheric lens surface, the possibility was realized of furnishing a projection objective of compact construction and having a high image quality.

In the division of this lens arrangement into six lens groups: a first lens group having a positive power, a second lens group a negative power, a third lens group a positive power, a fourth lens group a negative power, and a fifth and sixth lens group respectively a positive power, a preferred position of the aspheric surface is at the end of the second lens group. It is then arranged, in particular, on the last lens of the second lens group or at the beginning of the third lens group, and indeed preferably on the first lens of the third lens group. A correction of image errors in the region between the image field zone and the image field edge is possible by means

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

of this aspheric lens surface. In particular, the image errors of higher order, which become evident on considering sagittal sections can be corrected. Since these image errors apparent in sagittal section are particularly difficult to correct, this is a particularly valuable contribution. In an advantageous embodiment, only one lens has an aspheric surface. This has a positive effect on the production costs, since it is the production of highly accurate aspheric surfaces that requires considerable technological effort, which entails increased costs. It was only with the use of exactly one aspheric lens that it was possible to provide a very compact objective, in which case the additional costs for the aspheric lens are not important, since considerable cost savings were connected with the reduction of the required material and of the surfaces to be processed and tested.

By the measure of providing a lens arrangement that has at least a first waist, an aspheric surface before and an aspheric surface after the waist, a lens arrangement is produced which makes possible a high numerical aperture with high image quality, particularly for the DUV region. In particular, it is possible by the use of these aspheric surfaces to furnish a projection objective of short structure and high image quality. Objectives used in microlithography generally have a high material density over their whole length, so that the reduction of the length is connected with a considerable saving of material. Since only very high-grade materials can be used for projection objectives, particularly for microlithography, the required use of material has a severe effect on the production costs.

The aspheric surface arranged before the first waist can be arranged at the end of the first lens group or at the beginning of the second lens group. Furthermore, it has been found to be

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

advantageous to arrange an aspheric surface, arranged after the first waist, on the last lens of the second lens group or on the first lens of the third lens group.

The aspheric surface provided before the first waist in particular makes possible a targeted correction of coma in the region of the image field zone. This aspheric lens surface has only a slight effect on the skew spherical aberration in tangential section and in sagittal section. In contrast to this, the skew sagittal aberration, particularly in the region between the image field zone and image field edge, can be corrected by the aspheric lens surface after the waist.

The provision of a second aspheric lens surface is thus a worthwhile measure, in order to counter at high numerical aperture a reduction of image quality due to coma.

In a few cases of application, particularly with very high numerical aperture, it has been found to be favorable to provide a projection objective wherein the third lens group has a lens having an aspheric surface, and, in particular, the last lens of the third lens group has an aspheric surface.

It has been found to be advantageous to provide a first lens in the sixth lens group with an aspheric surface for a further correction of coma, especially in the region of the image field edge.

For this aspheric lens surface, the first lens of the sixth lens group has been found to be a particularly well suited position.

Furthermore, the numerical aperture can be increased, at constant image quality, by the provision of a further aspheric surface on the last lens of the third lens group.

It is an advantage of the invention to provide a refractive microlithographic projection objective, wherein all aspheric lens surfaces have a vertex radius (R) of at least 300-mm. Thus

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

the aspheric surfaces are provided on long radii, since the production and testing is easier for lens surfaces with long radii. These surfaces are easily accessible to processing equipment because of their low curvature. In particular, surfaces with long radii are accessible with Cartesian coordinates for tactile measurement processes.

It has been found to be advantageous to use at least two different materials for achromatization, for projection objectives designed for an illumination wavelength of less than 200 nm, because of the stronger dispersion of the lenses, even with the use of narrow-band light sources. In particular, fluorides, especially CaF₂, are known as suitable materials, besides quartz glass.

It has been found to be advantageous to provide at least two lenses of CaF₂, which are arranged before an aperture stop in the fifth lens group, for the correction of color transverse errors.

It has been found to be advantageous for the further correction of color errors to integrate an achromat after the aperture stop by means of a positive CaF₂ lens and a following negative quartz lens. This arrangement has a favorable effect on the correction of the spherical portions. In particular, longitudinal color errors can be corrected by the lenses after the aperture stop.

A reduction of the longitudinal error already results in general from the shortening of the length of the projection objective. Thus a good achromatization with a reduced use of CaF₂ lenses can be attained with the objective according to the invention.

Brief Description of the Drawings

The invention is described in more detail hereinafter with the aid of preferred

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

embodiments, in which:

- Fig. 1 shows a schematic illustration of a projection exposure device;
- Fig. 2 shows a lens section through a first lens arrangement of a projection objective with an aspheric lens surface;
- Fig. 3 shows a lens section through a second lens arrangement, which has two aspheric lens surfaces:
- Fig. 4 shows a lons section through a third lens arrangement, which has three aspheric lens surfaces;
- Figs. 5a-5g illustrate tangential transverse aberrations;
- Figs. 6a-6g illustrate sagittal transverse aberrations;
- Figs. 7a-7f illustrate groove errors of the third lens arrangement with the aid of sections;
- Fig. 8 shows a lens section through a fourth lens arrangement, which has three aspheric surfaces;
- Fig. 9 shows a lens section through a fifth lens arrangement, which has four aspheric surfaces; Fig. 10 shows a lens section through a sixth lens arrangement, which has four aspheric surfaces.

Detailed Description of Preferred Embodiments

The principle of the construction of a projection exposure device is first described with the aid of Fig. 1. The projection exposure device 1 has an illuminating device 3 and a projection objective 5. The projection objective includes a lens arrangement 19 with an aperture stop AP, an optical axis 7 being defined by the lens arrangement 19. A mask 9 is arranged between the illuminating device 3 and the projection objective 5, and is supported in the beam path by means

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

of a mask holder 11. Such masks 9 used in microlithography have a micrometer to nanometer structure, which is reduced by means of the projection objective 5 by a factor of up to 10, particularly a factor of four, and is imaged on an image plane 13. A substrate positioned by a substrate holder 17 or a wafer 15 is supported in the image plane 13. The minimum structures which are still resolvable depend on the wavelength λ of the light used for illumination, and also on the numerical aperture of the projection objective 5, the maximum attainable resolution of the projection exposure device 1 increasing with decreasing wavelength of the illuminating device 3 and with increasing numerical aperture of the projection objective 5.

The projection objective 5 contains, according to the invention, at least one aspheric surface to provide a high resolution.

Various embodiments of lens arrangements 19 are shown in Figs. 2-4 and 8-10.

These projection objectives 5 designed for more stringent requirements for image quality and for resolution, and in particular their lens arrangement 19, are described in more detail hereinafter. The data of the individual lenses L101-130, L201-230, L301-330, L401-429, L501-529, L601-629, can be found in detail in the associated tables. All the lens arrangements 19 have at least one aspheric lens surface 27.

These aspheric surfaces are described by the equation:

$$P(h) = \frac{\delta \cdot h \cdot h}{1 + \sqrt{1 - (1 - EX) \cdot \delta \cdot \delta \cdot h \cdot h}} + C_1 \left[h^4 + \ldots + C_n \right] h^{2n + 2} \delta = 1/R$$

(Z) 99023 PUS US Patent Application 09/760,066 Schuster Substitute Specification

in which P is the arrow height as a function of the radius h (height to the optical axis 7) with the aspheric constants C₁ through C_n given in the Tables. R is the vertex angle given in the Tables.

The lens arrangement 19 shown in Fig. 2 has 29 lenses L101-L129 and a plane parallel plate L-130. This lens arrangement 19 can be divided into six lens groups, which are denoted by LG1 for the first lens group through LG6 for the sixth lens group. The first, fifth and sixth lens groups have positive refractive power, while the second lens group LG2 and the fourth lens group LG4, by which a first waist 23 and a second waist 25 are formed, have negative refractive power. This lens arrangement 19 is designed for the wavelength $\lambda = 193.3$ nm which is produced by a KrF excimer laser, and has an aspheric lens surface 27. A structure width of 0.10 μ m is resolvable with this lens arrangement 19 at a numerical aperture of 0.75. On the object side, the light transmitted by the lens arrangement propagates in the form of a spherical wavefront. In the objective, the greatest deviation from the ideal wavefront, also denoted by the RMS factor, is $10.4 \text{ m}\lambda$ with respect to the wavelength $\lambda = 193.3$ nm. The image field diagonal is 28 mm. The constructional length from mask plane to object plane is only 1,000 mm, and the maximum diameter of a lens is 235 mm.

In this embodiment, this aspheric lens surface 27 is arranged on the side of the lens L110 remote from the illumination device.

The projection objective having the previously mentioned good performance data could

(Z) 99023 PUS US Patent Application 09/760,066 Schuster

Substitute Specification

for the first time be furnished with the use of this aspheric lens surface 27. This aspheric lens surface 27 serves to correct image errors and also to reduce the required constructional length, with image quality remaining constant. In particular, image errors of higher order in the region between the image zone and image field edge are corrected here by this aspheric surface 27. This correction brings about, in particular, ar increase in the image quality in the sagittal direction.

The dispersion of the available lens materials increases with shorter wavelengths.

Consequently, increased chromatic image errors arise in projection objectives for short wavelengths such as 193 nm or 157 nm. The usual embodiment for 193 nm therefore has quartz glass as the flint and CaF₂ as the crown, as lens materials for achromatization.

With an overall minimum use of the problematic CaF₂, care has to be taken in that a CaF₂ lens L114 in the third lens group LG3 places an increased requirement on the homogeneity of the material, since it is arranged far from the aperture stop AP. For this purpose, however, it has a moderate diameter, which substantially improves the availability of CaF₂ with an increased requirement.

For the correction of color transverse error, three CaF₂ lenses L119, L120, L121 are arranged in the fifth lcns group LG5, before the aperture stop AP. An achromat 37, consisting of a convex CaF₂ lens L122 and a following meniscus lens L123 of quartz glass are arranged directly behind the aperture stop AP. These CaF₂ lenses can be of lower quality than the CaF₂ lens L114, since quality deviations in the middle region can easily be simultaneously corrected for all image field regions (by lens rotation during adjustment).

A further CaF2 lcns L129 is arranged in the sixth lens group. It is possible by means of

(Z) 99023 PUS US Patent Application 09/760,066 Schuster Substitute Specification

this lens of CaF₂ to reduce the effects of lens heating and refractive index changes due to irradiation, named compaction.

The individual data for the lenses L 01-L130 can be found in Table 1. The optically utilized diameter of all the CaF₂ lenses is less than 235 mm. Since the availability of CaF₂ is furthermore limited in dependence on the diameter required, the required diameter of the CaF₂ lenses used is of central importance.

A lens arrangement 19 designed for the wavelength $\lambda = 248$ nm is shown in section in Fig. 3. This lens arrangement 19 has two aspheric lens surfaces 27, 29. The first aspheric lens surface 27 is arranged on the image side on the lens L210. It can also be provided to arrange this second aspheric lens surface 27 on the side of the lens L211 facing toward the illumination device. The two lenses L210 and L211 are predetermined for the reception of the aspheric lens surface 27. Provision can also be made to provide a meniscus lens having an aspheric lens surface instead of the lenses L210 and L211. The second aspheric lens surface 29 is arranged in the end region of the first lens group, on the side of the lens L205 remote from the illumination device 3. It can also be provided to arrange this aspheric lens surface 29 on the lens L206 following thereafter in the beginning of the second lens group.

A particularly great effect is obtained when the aspherics 27, 29 are arranged on lens surfaces at which the incident rays include a large angle with the respective surface normals. In this case the large variation of the angle of incidence is important. In Fig. 10, the value of sin i at the aspheric lens surface 31 reaches a value of up to 0.82. Because of this, the two mutually facing lens surfaces of lenses L210, L211 in this embodiment have a greater effect on the course

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

of the rays in comparison with the respective other lens surfaces of the corresponding lenses L210, L211.

With a length of 1,000 mm and a maximum lens diameter of 237.3 mm, this lens arrangement has a numerical aperture of 0.75 at a wavelength of 193.3 nm. The image field diagonal is 27.21 mm. A structure width of 0.15 μ m is resolvable. The greatest deviation from the ideal wavefront is 13.0 m λ . The exact lens data with which these performance data were attained can be found in Table 2.

A further embodiment of a lens arrangement 19 for the wavelength 248.38 nm is shown in Fig. 4. This lens arrangement 19 has three lenses L305, L310, L328 which respectively have an aspheric lens surface 27, 29, 31. The aspheric lens surfaces 27, 29 have been left at the positions given by Fig. 3. The coma of middle order can be adjusted for the image field zone by means of the aspheric lens surface 27. The repercussions on sections in the tangential direction and in the sagittal direction are then small.

The additional, third aspheric lens surface 31 is arranged on the mask side on the lens

L328. The aspheric lens surface 31 supports come correction toward the image field edge.

By means of these three aspheric lens surfaces 27, 29, 31, there are attained, at a wavelength of 248.38 nm and at a length of only 1,000 mm and a maximum lens diameter of 247.2 mm, the further increased numerical aperture of 0.77 and a structure width of 0.14 μ m which can be well resolved in the whole image field. The maximum deviation from the ideal wavefront is 12.0 m λ .

In order to keep the diameter of the lenses in LG5 small, and in order for a Petzval sum

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

which, advantageously for the system, should be kept nearly zero, the three lenses L312, L313, L314 in the third lens group LG3 are enlarged. The thicknesses, and thus the diameters, of other lenses, particularly the lenses of the first group LG1, have been reduced in order to furnish the required axial constructional space for these three lenses L312-L314. This is an excellent way to arrange very large image fields and apertures in a restricted constructional space.

The high image quality which is attained by this lens arrangement can be seen in Figs. 5a-5g, 6a-6g and 7a-7f.

Figs. 5a-5g give the meridional transverse aberration DYM for the image height Y' (in mm). All show an outstanding course up to the highest DW'.

Figs. 6a-6g give the sagittal transverse aberrations DZS as a function of the half aperture angle DW' for the same image heights nm).

Figs. 7a-7f give the groove error DYS, which is nearly zero throughout.

The exact lens data can be found in Table 3, the aspheric lens surfaces 27, 29, 31 have a considerable participation in the high image quality which can be ensured.

A further lens arrangement for the wavelength $\lambda = 248.38$ nm is shown in Fig. 8. With a length of only 1,000 mm, this lens arrangement 19 has, with only three aspheric lens surfaces 27, 29, 31, a numerical aperture of 0.8; a structure width of 0.13 μ m is well resolvable in the whole image field, whose diagonal is 27.21 mm. The maximum lens diameter is 255 mm and occurs in the region of the fifth lens group LG5. The lens diameter is unusually small for the numerical aperture of 0.8 at an image field having a 27.21 mm diagonal. All three aspheric lens surfaces 27, 29, 31 are in the front lens groups LG1-LG3 of the lens arrangement 19. The deviation from

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

the ideal wavefront is only 9.2 mh in this lens arrangement.

The exact lens data of this lens arrangement can be found in Table 4.

A further increase of the numerical aperture, from 0.8 to 0.85, could be attained by the provision of a further, fourth aspheric 33 on the side of the lens L513 remote from the illuminating device. This high numerical aperture, from which there results an acceptance angle of 116.4°, as against an angle of 88.8° with a numerical aperture of 0.70, is unparalleled for the image field with diagonal 27.21 mm. The well resolvable structure width is 0.12 μ m, and the maximum deviation from the ideal wavefront is only 7.0 m λ . Such a lens arrangement 19 is shown in Fig. 9, and the exact lens data can be found in Table 5.

In comparison with the preceding embodiments of Figs. 1-3 and with the cited DE 198 18 444 A, the last two lenses are united into one lens in this lens arrangement 19. By this measure, in addition to the savings in lens production, a lens mounting can be saved in the end region, so that constructional space is created for auxiliary devices, especially for a focus sensor.

A lens arrangement 19 designed for the wavelength $\lambda = 157.63$ nm is shown in Fig. 10. The image field which can be illuminated with this lens arrangement has been reduced to 6×13 mm, with an image field diagonal of 143 mm, and is adapted for the stitching process.

With a length of only 579.5 mm and a maximum diameter of 167 mm, and with four aspheric lens surfaces 27, 29, 31, 33, a numerical aperture of 0.85 and a well resolvable structure width of 0.07 μ m were attained. The deviation from the ideal wavefront is 9.5 m λ at the wavelength $\lambda = 157.63$ nm.

The absorption of quartz lenses is quite high because of the short wavelength, so that

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification

recourse was increasingly had to CaF₂ as the lens material. Single quartz glass lenses are provided in the region of the waists 23, 25, i.e., in the second and fourth lens groups LG2 and LG4. These quartz glass lenses are to have the highest possible transmission. A further lens of quartz glass, in the form of a meniscus lens L625, is provided in the lens group LG5 to form an achromat. Furthermore in lens group LG6, the lens L628 having an aspheric lens surface is of quartz glass. The aspheric surface 33 is thus constituted of the material which is easier to process.

The color longitudinal error of this lens arrangement 19 is thus very small, even at this very high numerical aperture.

The embodiments hereinabove show that good performance data can be attained without aspheric surfaces (27, 29, 31, 33) having large diameters, especially in the fifth lens group. The small aspheric lens surfaces utilized can easily be made and tested.

These lens arrangements 19 illustrated in the embodiments show solely the design space set out by the claims. Of course, the features according to the claims and their combinations, put in concrete terms with the aid of the embodiments, can be combined with each other.

(Z) 99023 PUS US Patent Application 09/760,066 Schuster

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L104	375.05253		1160		80.492	
	-496.09705	.75		S102	83.813	
L105	191.46102		2529	He	83.813	
	-1207.32624	.75		SIQ2	81.276	
L105	180.94629		5881	He	80.032	
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L110	-112.01095	6.00		He	62.911	
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L111	-225.51622	143	0/6	He	7 5 .868	
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L112	5312.93388	.7500		He	81.928	
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L113	344.71979	.7500		Hę	101.920	
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L114	165.51327	.7500		He	111.237	
	7755.09540	39.67		CAF2	101.552	
L115	195.28524	.7500		He	99.535	
	119.99272	23.89		SIQ2	87.267	
L116	-452,93918	32.27		He	72,012	
	287.33119	6.000		SIO2	70.763	
L117	-218.82578	20. 782		He	56,677	
	156.44429	6.0000		SIO2	66.150	
L118	-103.90786	40.575		He	66.003	
•	5916.68891	6.4932		S1O2	66.694	
L119	-344.93456	13.333	6	Hę	80.536	
	-185.11801	19.858	1	CAF21	82.79D	
L120	-11871,72431	.7500		He	86.174	
	174.34079	38,509,	5	CAF2:	100.670	
L121	586.98079	.750 ()		Нe	102.666	
	414.20537	31.6\$15	5 6	CAF2.	111.739	
•- 1	ntinity	.7500	}	-le	112.097	•
	stop	3.6849	_ _ //	l e	111.399	
11	ntinity	.000d	}	ie	111.399	•
		1.2586	- }	ie	111.830	
4	84.64742	45.7670	ا د			
L123	414.78783	17.9539	T	t_	114.801	
	234.72451	14.5097			114,410	
		[]	"		113.062	
		ŀ	4			
		ŀ				.
	.•	•				
		ŀ				
		ŀ	-			

PCT/EP99/10233

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			<u> </u>	<u></u>	
WO 00/7	0407			Table 1	
					•
				page 2	
	-593.08647	14.	730	He	
L124	-323.13567		874	5102	114.454
• •	-229.06128	.750	0	He	114.235
L125	180.27184	31.4		SiO2	117.505
	652.02194	.750		He	105.659
L126	143.20049	28.2		\$102	103,598
	383.51531	14.7		He	91.476
L127	-2122.47818	14.1		SIO2	88.206
	312.60012	1.31	•	He	85.843
. L128	111.92162	45.5		\$102	74.816
	53.69539	2.25	•	He	66.708
L129	51.14657	27.3		CAF2	40.084
	492.53747	3.78		He-	39.074
	infinity	3,00		SIQ2	32.621
	infinity	12.0		G102	29.508
	infinity				27.848
					14.021
				•	
•					
Aspheric Cor					
- TENDITO COI	<u>istants:</u>				
Coefficients of	the aspheric surfa	ce n			
	•				
	[where <u>n</u> is	321][
EX = 0.0000	} 				
				į.	
C1 = 0,61839643	* 10 ⁻⁸				
C 2 = 0.11347761	* 10***				
C 3 = 0,32783915	10-15				
	-		٠		
C 4 = -0.22000186	* 10 ⁻²⁰				
	. •				
		.			
		·			
			; ;		
	: !		, !		

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-	ļ			Table 2		PCT/EP99/10233
m736a						
	Dadii Thiala	!	١.	page I		
Lenses	Radii Thicknesse	* 5	Glas,	ses. ½×L	ens Diameter	
		ŀ				
	infinity 16.6148					•
L201	-140.92104 7.0000	١,	,,,,,	60.752		
	-4944.48962 4.5190	٦	102	61.267		
L202	-985.90856 16.4036		102	67.230	•	
	-191.79393 .7500	٠, ا	102	68.409		
L203	18376.81346 16.5880	s	102	70.127		
1204	-262.28779 .7500			73.993 74.959		
L204	417.82018 .21.1310	s	02	77.129		
L205	-356.76055 .7500	•		77.193		
C205	185.38468 23.3034	S	Q2	74.782		
1206	-1198.61550 A7500 192.13950 11.8744			73.634		
		S	O 2	68.213		
L207	101.15610 27.6353 -404.17514 7.0000			61.022		
	129.70591 24.1893	S	02	60.533	٠.	
L208	-235.98146 7.0584	P1		58.732		•
	-203.88450 .7500	31	02	59.144		
L209	-241.72595 7,0000	SIC	22	50.201		
1040	196.25453 33.3115	"		60.490 65.017		
L210	-122.14995	Sic	2	66.412		
L211	-454.65265 A 10.8840			77.783		•
	-263.01247 22.6024 -149.71102 1.6818	Sic	2	B1.685		
L212	-149.71102 1.6818 -23862.31899 43,2680			86.708		
	-166.87798 .7500	SIC	2	104.023		
L213	340.37670 44,9408	ļ _,_		106.012		
	-355.50943 .7500	SIC	2	115.503		
L214	160.11879 41.8646	SIO	,	115.398		
4.4.5	4450.50491 7500		2	102.982		
L215	172.51429 14.8261	SIO	,	100.763		
L216	116.88490 35.9100		Ĩ	85.869 74.187		
EZ 10	395.46894 7.0000	SIO	2	72.771		
L217	178.01469 28.0010 176.03301 7.0000			66.083		
	176.03301 7.0000 188.41213 36.7224	S102	•	65.613		
L218	440 4000	L.,		66.293		
•	683.42330 17 1440	5102		66.917		
L219	-350.01763 19.1589	51O2	-	80.240		
1.000	-194.58551 .7514	7.02		82,329		
L220	8249.50149 35.3656	SIO2		87.159		
L221	-213.88820 .7500			99.995 103.494		
1221	657,56358 31.3375	102		114,555		
***	428.74102 .0000			115.245		•
	P4= -			116.016		
Ľ222	820 20con			116.016		
	-520.84842 18.4284	102		118.196		
L2Z3	330.19065 37.7588 s	02	•	118.605		
	-672.92481 23.8692	1 ~~		118.273		
				117.550		
	,					
						-
	·,					
		}				
		1			•	
	1					

PCT/EP99/10233

C 2 = -0.22884234 - 10-11

C 3 = -0,23852814 + 10-18

C 4 = -0.19091022 - 10-19

C 5 = 0.27737562 - 10-23

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	-								page 1		· ·.			
	m745a		T				Į							
	Lenses		Radii		Thicknes	se	\$ (Hass	es ½	ŻΧL	ens Diai	meter	•	
												110101		
		:	infinit	y	17.8520									
	L 301		-131.57		7.0000	٠.	۰	102		.958				
		•	-195.669	940	.7500		٦	02		.490				
	L302		-254.663	366	8.4334		s	102		.933 .844				
	L303		-201.644	180			٠.	_		.386				
	L 003		-775.657		14.0058		S	02		629				
	L304		-220.445 569,586	30	.7500		ľ			678			1	
			-308.251	PO RA	18.8956		SI	02	72.	689				
	L305		202.5803	13	.7500 20.7802		۱.			876				
			-1120.20	883	A7500		SI	02		232	•			
	L306		203.0339	5	12.1137		SI	12		282				
	307		102.6151	2	26.3989			72	59.:	974		•		
	L307		-372.053	36	7.0000		Sic	2	59.:					
ı	.308		144.4088 -207.9362	9	23.3868				58.3					
			·184.6593	(0 2	7.0303		SIC	2	58.7	190				
ι	309		-201.9772	20	.7500 7.0000			_	59.9	185				
			214.5771	5	33.1495		SIC)2 	60.2					
L	310		-121.8070	2	7.0411		SIÇ		€5,7	•				
	3		-398.2635	3 A	9.7571			[67 <u>-2</u> 79.0					
L	311		242.4031		22.4968		SIO	2	81,9					
L:	312		146.7633	9	.7563				87.3	-				
			2729,1996 158.3700				SIO	2	104.	_				
L	313	:	356.37642		.7762 52.1448				107.2					
		•	341.95165	_	1.1921		SIO	Í	118,5					
L	314.		59.83842		44.6278		SIO	}	118.5					
13	15	2	234.73586	5.	7698			Ī	105.6 102.7					
-		7	72.14697 19.53455		6.8360		5102		88.03					
43	16		392.52196		86.6804		Į		75.66					
		1	71.18767		'.0000 '9.4986		102		74.24	6				
13	17	-	76.75022		.0000		102		67.27					
1.54		18	36.50720		8.4360	Ì	102		66.843					
L31		-1	13.94008		.0213	9	102		67.938					
L31	9	89	93.30270 27.77804		7.7405				58.650 82.870					
•••	_	-1	92.72640		3.9809	۶.	102		85.090					
L32	0	-3	571.89972		513 1.3608	_			89.918					
		-2	9.35555		500 500	\$	O2		103.88					•
L32	1	67	5.38083		.6220	8	02		106.57					
		-44	9.16650	.00	000	•	-		119.19 119.960					
	•	In	finity op		3420		•	l .	120.99					
Ĺ322	•	77	l.53843		000			•	120.991					
		-52	5.59771		.6490 .4504	SI	D2		123.568					
_323		330	0.53202		4504 0766	ь.	Ĺ.		124.005	;				
		-71	2.47656		6787	Si)2 	٠	123.477					
						ĺ		•	122,707					
	•	ļ				ĺ								
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		i	٠.											
		į												

C 4 = -0,87762405 - 10-21

WO 00/70407		Table 3	Demonstration
		page 2	PCT/EP99/10233
L324 -250.00950	10.0000		
-513.10270	10.0000 SI 14.8392	1 1	
L325 -344.63359		121,995 D2 121,081	
	.7500	121.530	
•	34.7977 SI		
	.7510	99.992	
	29.7785 SI	37.000	
294,53397 L328 -3521.27938 A	18.8869	82.024	
	11.4951 Sid .7814	75.848 65.798	
1000	27.8602 SI		
	1.9089	36.734	•
	31.0202 SI	2 36.281	
٠٠٠٠	1.9528	28.934	
	12.0000	28.382	
infinity		13.503	
Aspharia Can			•
Aspheric Constants:			
Coefficients of the asphe	eric surface n	·	
- · · · · · · · · · · · · · · · · · · ·	where <u>n</u> is 29]		
C 1= 0.49600479 10°			
C 2 = 0,31354487 * 10 ⁻¹¹			
C 3 =-0,55827200 10-16			•
C 4 = 0,44673095 10 ⁻¹⁹			
C 5 = -0.73057048 - 10 ⁻²³			
$C6 = 0.91524489 + 10^{-27}$			
Coefficients of the asphe	ric surface <u>n</u> :		
Γτω	here <u>n</u> is 27]		
= -0,22247325 • 10°			
C 1 = 0,24479896 10 ⁻⁷			
C 2= -0.22713172 - 10-11			
C 3 = 0,36324126 - 10 ⁻¹⁶			•
C 4 = -0,17823969 - 10 ⁻¹⁸			
C 5 = 0.26799048 + 10 ⁻²²		1	
C 6 = -0.27403392 • 10 ⁻²⁷			
Coefficients of the aspher	ic surface n		
ı	here <u>n</u> is 31]		
EX = 0			
C 1 = -0,45136584 - 10-09			_
C 2= 0,34745936 - 10 ⁻¹²			•
C 3 = 0.11805250 • 10 ⁻¹⁷			
1: 4 = 0 0=>== 1.4471		r 1	

• ,	WO 00/70407		. Ta	ble 4	<u> —</u>	PCT/EP99/10233
m791a		l	pa	age l		
Lenses	Dadii Thia		CI			
	Radii Thickness	es	Glasse	^S ⅓xL	ens Diameter	
L401	infinity 11.4557	1		61,339		
L4U)	-273.19568 7.0000		102	62,263		
L402	-277.09708 .7000 -861.38886 8.9922]	63,765		
	-851,38886 8.9922 -339,26281 .7000	\$	102	64.989		
L403	118124.1371911.2867		102	65.826		
	-365.70154 .7000	`	102	66.916 67,416		
L404	685.10936 13.1651	s	02	67.995		
L405	-485.98278 7000			68.012		
L405	387.56973 17.2335	S	02	67.247		
L406	-473.09537 A .7000 268.03965 9,9216	_]	66,728		
- : • •	149.12863 23.8122	S	02	62.508		
L407	-184.82383 7.0000	8	02	58.531		
	176.30719 21,4194	٦	\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\\	58.029	•	
1408	-186.59114 7.0000	SI	D2	57,646 58.045		
L409	218.73570 29.5024			63,556		
L409	-129.31068 7.0000	SI	D 2	65.030		
L410	-531.44773 A 17.2306 -307.52016 22.4527			76,481		
-1.0	-307.52016 22.4527 -148.36184 .7000	SI	D 2	85.643		
L411	-1302.18676 41.0516	01/		88.946		
	-162.48723 .7000	SI	12	105.065		
L412	621.16978 41.1387	SIC] 52	107.106 118.007		
L413	-294.49119 .7000			118.347		
C4 13	160.06951 49.7378	\$10	2	109.803		
L414	-2770.71439 A7000 152.16529 16.7403			107.961		
	152.16529 16.7403 106.43165 39.9369	SIC] 2	89.160		
L415	-530.55958 7,0000	ŚĩÇ	12	76.189		
1	170.63853 31,4993	1	[74.955 6 8. 381		
L416	164.61084 7.0000	Sic	2	67.993		
L417	262.65931 36.2904			69.679		
••••	113,57141 8.4328 772,56149 21,7682	SIC	2	70.272		
L418	7/2.56149 21.7682 278.33295 16.4890		Ţ	85.377		
	198.24799 ,8689	SIO	ř	87.710		
L419	3464.54038 37.5900	SIO	, .	92.554		
1.400	214.63481 1.1929		Ī	107.590 111.045		
L420	2970.07848 32,3261	SIO	\$	122.434		
L421	350.93217 2.5303			123.849		
M76 !	1499.34256 25.8265 -561.19644 .0000	\$102	2	127.128		
	-561.19644 ,0000 - infinity ,7510			127.371		•
•	stop .0000		,	126,559	•	
L422	821.09016 39.5191	\$102		126,559		•
1.400	-1995.20557 .7000	[127.453 127.499		
L423	337.02437 41.8147	\$102		126.619		•
	-559.23025 25.0233		1	125.851		
	.			- •		
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PCT/EP99/10233

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W	D 00/704	07			. 4	Table 4
L424	245	0.00004	-			page 2
F-72-7		2.66564	7.0000	SI¢	2	124,960
L425.		1.19390	9.7905			125.057
C423.		2.17516	41.0678	Sid	2.	124.887
L426		2.55195	.7000	į		125.845
2420		04614	37.2406	Sid	2	104.033
L427		88892	7008	i		101.079
B42,		31280	31.5532	SIQ	2	85,742
L428		69473	15.2917	. !		79.561
E-120	:	1.93157	7.8700	sıq	2	74.994
L429	:	90273	.7011			66.830
-125	- 1	95136	55.0835	sıq	2	61.517
	I	13980	15.0000	ì		32.177
	infir		.0001	ł		13.603
	infi	ity.		į		13.603
	i	•				
A == 1-						
Aspheric	<u>c Cons</u>	tants:				
Coefficie	ents Af	the asn	heric surf			
Common	onts Or					
EX = 0,453	24707 6	407	where <u>n</u> i	s 27][
C1 = 0,400	27004	10-				
C 1 = 0,120	2/601 7	10"				
C2 = -0.162						
C3 = -0.416				ļ		
C4 = 0.384	40137 🕈	10.19				
C 5 = -0,150	96918	10-23				
C 6 = -0,848				Ī		
•						
Coefficier	nts of t	he asoh	eric surfac	ا بم م		
	ا دو سد					
EX = 0	!		where <u>n</u> is	29]		
C 1 = -0,974	52539 🕇	10-7				
C 2 = 0.3259	1079 +	10-11		l		
C 3 = 0,9742	6255 *	10-16		į		
C4 = -0.846				į		
C 5 = -0.123						
C 6 = 0.1444						
0 0 - 0, 14444	3/13 -	10.21				
Caa8=:-				ŀ		
Coefficient	ts of th				.	
EX = 0 ·	·-	[74	here <u>n</u> is 3	33]		
C1 = 0.5314	44 27 = 4		, –	- i		
				Į		•
C 2 = 0.2183				[
C 3 = 0,2280				ŀ		
C4 = -0.8780				. [٠	
C = 0.42592						
Ç 6 ≈ -0,8570				-		

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	WO 00/70407			Table 5 page 1	<u>ب</u> .	PCT/EP99/10233
j430a	ļ			hage i	·	
Lenses	Radii Thickness	es	Glas	see 14 - 1'	- D:	
	İ	} .		••• /2 X L	ens Diameter.	•
	infinity 9,9853					
L501	000 00-		.	61,649		
2001	-265.92659 5.0000 857.92226 5.9813	\$	102	62,237		
L502		ł _]	. 65.916		
	-2654.69270 14.4343 -244.65690 .7500	١٤	102	66,990		
L503	1038.40194 15.9955	,	102	68.482		
	-333.95446 7500	"	102	71.883		
L504	359.47562 18.5128	9	02	. 72.880		
	-532.67816 .7500	ľ	2	74.430		
L505	213.38035 21.4562	s	02	74.416 72.985		
L506	-1441.22634 A7500		_	72.045		
2000	251.90156 6.5306 115.92184 28.4856	S	02	67.809	•	
L507	-0.100			62.818		
	-267.21040 6.0000 175.09702 23.2443	SI	C 2	62.411	•	
L508	-213.08557 6.0000			61.923		
•	199.61141 30.8791	21	02	62.365		
L509	-158.73046 6.0337	SIC	m2	68.251		
1 = 4 =	-1108.92217 A10.9048		۲	69.962		
Ŀ510	-314.37706 20.6413	SIC	2	81,119		•
1 544	-169.59197 .8014		Ť ·	84.163 88.902		
L511	-3239.97175 43.6396	SIC	2	106.289	•	
L512	-168.44726 .7500 495.41910 48.8975		}	108,724		
-	495.41910 48.8975 -288.85737 .7500	Sic	2	123.274		
L513	153.24868 48.7613	E10		123.687		
	920,32139 A .7500	SIO	۲	113.393		
L514	163.02602 15.7110	SIO		111.134		,
L515	124.97610 44.2564		Ī	98.188		
L313	422.99493 6.0000	SIO	2	84.961 83.633		
L516	184,60620 31,4985			76,498		
	-241.93022 6.0000 158.30899 51.3978	SIQ2	\$	76.180		
L517	58.30899 51.3978 -117.43130 6.5332	L		77.396		
	2476.47953 21.4666	\$102	7	78.345		
L518	-311.36041 15.2223	\$102		98.459		
1540	-221.58556 .7500	102	1	101.209	·	
L519	934.37047 37.6761	\$102		105,324 122,239		
L520	216.75809 .7500	_		125.425		
	3623.94786 39.6266 -370.69232 1.1289	\$102		146.583		
L521	1200 00044			148.219		
	-613.71745 .0000	¥02	l	157.194		
	infinity 7500			157.954		
L 52 2	stop .0000	1		158.061		
W4 <u>4</u>	709.88915 36.2662 5	102		158.061		•
L523	-1035.75796 .7500	1		160.170		
	313.44889 58.8000 S	102		160.137 155.263		
	-1048.56219 28.7484			153,730		
	!					
	İ	}				•
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₩O 00 <i>/1</i>	0407		Table 5 page 2		PCT/EP99/10233
	28.67790 15,0000	\$102			• .
	283.32936 14.7084 40.24577 23.9839	1 100	148,826		
-3	05.19883 .7510	\$102	148.336 148.189		
	52.28321 42.3546 34.50964 .7531	\$102	114.055 109.924		
i	24.56784 31.8554	\$102	91.106		
L528 -2	8987.53974 7.4387	\$102	86.038 82.126		
	6.02224 .8631	S!02	72.044		
13	41.25511 15.0000	102	67.036 37.374	•	
,	finity0001 Sinity-		13.604	•	
	y -		13.804		
	<u>.</u>				
Aspheric Con			}		
Coefficients of	the aspheric surface n			•	
EX = -0,2701288	[where n is 26	a			
C 1 = -0,480140	9 * 10 ⁻⁷				
C 2 = 0.3007583 C 3 = 0.3492294	i •				
C 4 = 0.2694630					
C 5 = -0,5825063					
C 6 = 0,6899139		ľ			
Coefficients of	the aspheric surface r	1			
EX = 0,41249481		1			
C 1 =-0,38239182 C 2 =-0,14976009					
C 3 =-0,25208193					
C 4 =-0,78282126 C 5 = 0,13017800					
C 6 =-0,14205614					
Coefficients of	the earlier - C		-	•	
· ·	the aspheric surface n [where n is 33		,	•	
EX = 0,26320110 C 1 = 0,27448935	10	1	,		
C 2 =-0,18100074		}			
C 3 = 0,58696756	• 10 ⁻¹⁷				٠
C 4 =-0,58955753 C 5 = 0,16526308	í				
C 6 =-0,25708759	i				ţ
	٠,				•

WO 00/70407

Table 5 page 3

PCT/EP99/10233

Coefficients of the aspheric surface n [where n is 31],

EX =-0.96865859 - 105 C 1 =-0.42411179 - 10-

C 2 = 0.12306068 · 10-12

C 3 = 0,69229786 • 10-17 C 4 = 0,80135737 • 10-20

C 5 ≈-0,14022540 + 10-23

C 6 = 0.79827308 • 10-20

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m767a			page	, 1	•	,
Lenses	Radii Thicknesses	1	Flasses	1/2 x	Lens Diameter	
	Imorniosbob			7 + 72	Don's Diameter	
	infinity 5.9005	l				
L601	infinity 5.9005	N	2 AF2	32.429		
	243.24465 5.2309	H	I .	32,780		
L602	2472.77263 9.2265		F2	35.323 36.825		
	-132.46523 .3958	H	l .	37,854		
L603	544.60759 8.6087 -188.98512 .6007		AF2	40.080		
L604	-188.98512 .6007 180.26444 10.3984	H	1	40.516		
	-394.70139 .4244	He	F2	41.764		
1505	101.06312 12.8236		F2	41.743 40.955		
LEAR	-691.58627 A .5111	Не	1	40.455		
L606	135.75849 3.1245 57.03094 16.2396		F2	37.553	•	
L607	57.03094 16.2396 -258.26919 5.9149	He	F2	34.284		
	116.53669 10.9654	He		33,871		
L608	-142.54676 3.2195	SI	1	33.188 33.372		•
L609	100.09171 16.1921	He		35,360		
1009	-83.03185 3.2311 -453.73264 A 5.1711	SIC	t .	35.264		
L610	-167.92924 12.0560	He CA	I	41.718		
	-93.29791 .4204	He	1	43.453 47.010		
L611	-1270.46545 24.2891	CA		56.224		
L512	-90.89540 1.1471	He	1	58.224		
6012	266.81271 25.6379 -171.23687 .3519	CA	i	66,498		
L613	82.41217 26.8409	He CA		66.755		
	529.17259 A .5132	He	1	61.351 60.098		
L614	81.87977 8.2278	CA	2	50.462		
L615	64.06536 22.9801 -259.83061 3.3437	He		44.346		
2015	-259.83061 3.3437 124.29419 13.5357	SIC	12	43.473		
L618	-197.29109 3.0000	SIC	2	40.266 39.809		
L617	87.83707 24.5613	He	}	39.571		
2017	64.97274 4.6170 1947.71288 9.3909	SIO	2	40.050		
L518	1947.71288 9.3909 -182.16003 7.8052	He CAF	12	49.830		
•	118.82950 ,3753	He		51.480 5 3,449		
L619	-633.93522 19.7976	CAF	2	63.119		
L620	115.14087 .3706	He		64.793		
1020	2647,04517 19.8039 -197,41705 2,7167	CAF	12	75.458		
L621	658.45083 30,1057	He CAF		75.413		
••	322.45899 .0001	He	<u>٠</u>	81.369 82.659		
	infinity 3948	He		82.583		
	stop0000 395.84774 16.8734	L		82.583		
	-535.79877 .3500	CAF He	2	83.488		
	165.28880 28.1341	CAF	! 2	83.449 80.761		
	- 398.21798 15.5667	He	1	80.133		
						4
	·•					
			'			

Wo	00/70407	
L624	4700	
-42-4	-175.54365 7.9803 SIC)
L625 .	-265 73712 41 and	
1	-156 06204 A	
L626	79.45912	
•	199.26460 3500	
L827	67 01872 45 45	
	140.01631 8.6050 J."	- 7
L628	2265.71693 A4.0939	2
L629	167.06050 2.0915	_
-010	102.24013 24.5664 CAF	2
	9,4740 NB	
	UNENDL .0001 NP	
•		
Aspheric C	<u></u>	
Aspheric C	<u>onstants:</u>	
Coefficients	of the same	
	of the aspheric surface n:	
EX≃ -0,798094	[where n is 29]	
C 1 = -0.21353	640 * 10*5	
C 2 = 0.56257	- 1010	
C 3 =-0,391229	39-10-14	
C 4 =-0,240897	'66 10 ⁻¹⁸	
C 5 = 0,302589	8211022	
C 6 = 0,143792	3 - 10-25	
Coefficients		
o correctents	of the aspheric surface n:	
- EX ≈0,1660595	101	
C 1 = 0.1244971	9 110"	
C 2 = -0,39565 +	10	
C3 = -0.1024174	11 10-14	
C 4= -0.1963148	5 10.17	
C 5 = 0,11604236 C 5 = 0,4669584	5 * 10-20	
	i l	
Coefficients of	the aspheric surface n:	
	· · · · · · · · · · · · · · · · · · ·	
EX = 0,1614147 *	100 [where n is 33]	
C 1 = 0,14130508	*10-7	
C 2 =0,9747553	10111	
$C_{3} = 0.20478684$	+ 10 ⁻¹⁵	
C4 = -0.17732262	- 10-18	
C 5 = 0,29715991	10-22	
C 6 = -0,19032581	10 ⁻²⁶	
	: I	

Table 6 " PCT/EP99/10233 page 2 79.485 78.592 78.015 78.036 60.151 57.925 48.063 45.305 43.177 38.352 34.878 22.044 7.166 7.166

WO 00/70407

Table 6
page 3

PCT/EP99/10233

Coefficients of the aspheric surface n:

[where n is 31

EX = 0 C 1 = -0,18139679 - 10⁻⁷ C 2 = 0,26109059 • 10⁻¹¹ C 3 = 0,23340548 • 10⁻¹⁴ C 4 = 0,29943791 • 10⁻¹⁷

 $C = -0.13596787 * 10^{-20}$ $C 6 = 0.21788235 * 10^{-24}$

21-N

front of and/or behind the first narrowing.

Abstract of the Disclosure

The invention relates to a projection lens comprising a lens assembly that has at least one first narrowing of the group of light beams. A lens with a non-spherical surface is located in

(Z) 99023 PUS
US Patent Application 09/760,066
Schuster
Substitute Specification